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Patent Application No. 10/618,536 Customer Number: 42717

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PALIENA Applicant: Docket No.: 24061.485 Jing Cheng Lin, et al. (TSMC2002-0360) § § § Serial No.: 10/618,536 Thien F. Tran Examiner: Filing Date: June 11, 2003 Art Unit: 2811 § For: Adhesion Copper and Etch Stop Layer for Copper Alloy Conf. No.: 5026

RESPONSE TO RESTRICTION REQUIREMENT

Mail Stop: Amendment Commissioner for Patents PO Box 1450 Alexandria, VA 22313-1450

Dear Sir:

In response to the Office Action mailed August 20, 2004, applicant hereby elects, Group II, Claims 1-18 and 30-32, which is drawn to a process for making semiconductor devices.

Applicant's election is made with traverse on the grounds that the embodiments delineated by the examiner are not patentably distinct and therefore constitute a single invention concept.

An early action on the merits is respectfully requested.

Respectfully submitted,

David M. O'Dell Reg. No. 42,044

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CERTIFICATE OF MAILING

I hereby certify that this correspondence is being deposited with the United States Postal Service as first class mail in an envelope addressed to: Mail Stop: Amendment, Commissioner For Patents, PO Box 1450, Alexandria, VA 22313-1450 on the date below.

Name

10-20-04

Date